



# Molecular beam epitaxy of Cs-Sb thin films: structure-oriented growth of high efficiency photocathodes

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CLASSE, Cornell University









#### **Maxson group**





#### Arias group





#### Shen group





#### **Hines group**







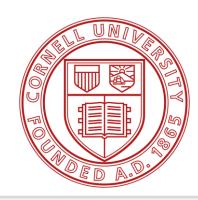












https://cbb.cornell.edu/

https://www.paradim.org/







- Motivation:
  - $-Cs_3Sb$  for brighter electron beams
  - -Surface disorder and emittance degradation
- Methods:

-RHEED monitored molecular beam epitaxy

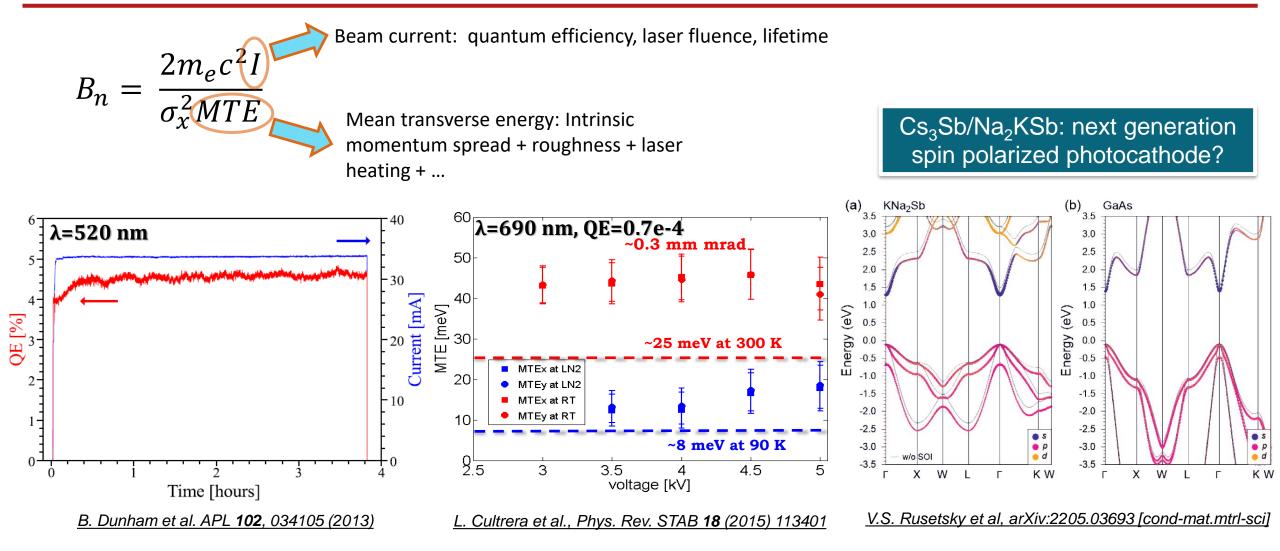
- Results: epitaxy of Cs<sub>3</sub>Sb phase! (first time!) – First band structure measurements of Cs<sub>3</sub>Sb thin films
- Results: new phase!

-Atomically smooth CsSb films: a visible light photoemitter with enhanced oxygen robustness

Future work and conclusions



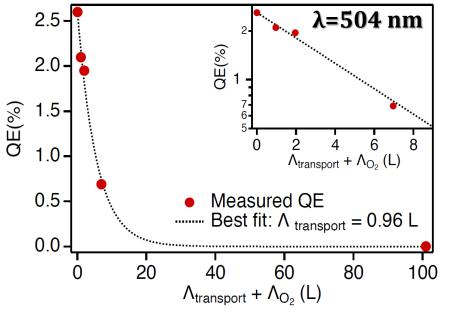


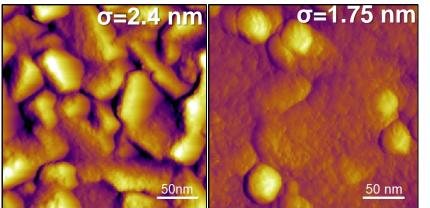




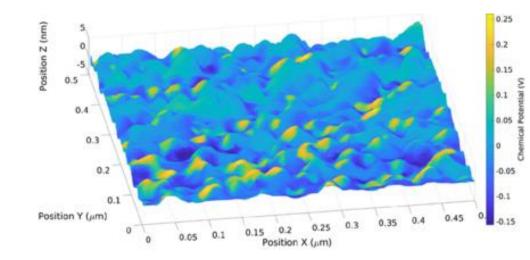
## Drawbacks: reactive, disordered







A. Galdi, et al. The Journal of Chemical Physics 153,144705 (2020) A Galdi, et al. Applied Physics Letters 118 (24), 244101 Why does this matter for applications? Because both heterogeneity enhaced by oxidation and roughness degrade MTE (besides QE degradation in poor vacuum)



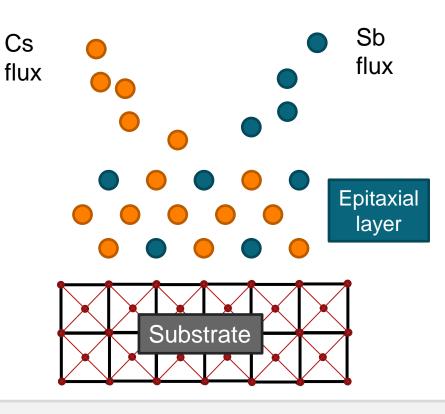
 $\Delta MTE = 25 meV$ @ 10 MV/m compare to measured: 42 meV@300K 15meV@90K

Measured surface and surface potential of a Cs<sub>3</sub>Sb photocathode G. S. Gevorkyan, PRAB **21**, 093401 (2018)





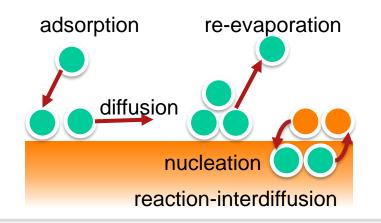
Epitaxy is the growth of a crystal layer with one or more well-defined orientations with respect to an underlying crystal seed layer (usually a single crystal substrate)



Epitaxial single-oriented films would allow:

- Roughness control
- Orientation control  $\rightarrow$  surface potential control
- Measurements of intrinsic properties (optical constants, band structure, intrinsic MTE...)

1) Choose the method: MBE	
2) Select suitable substrates	
3) Identify suitable growth conditions	

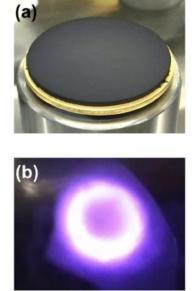


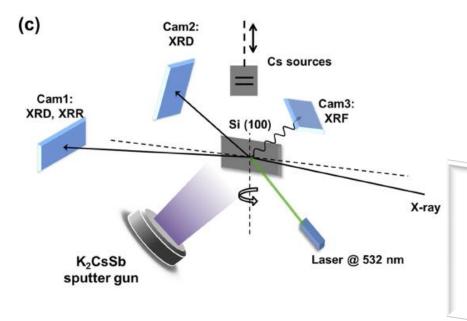


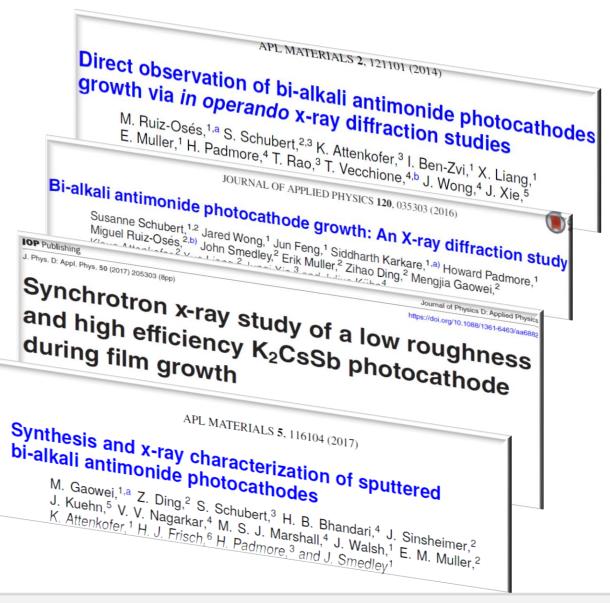
#### **Previous results**



Our work builds on many experimental results obtained via *in-operando* characterization of the growth of alkali antimonide thin films with different techniques.

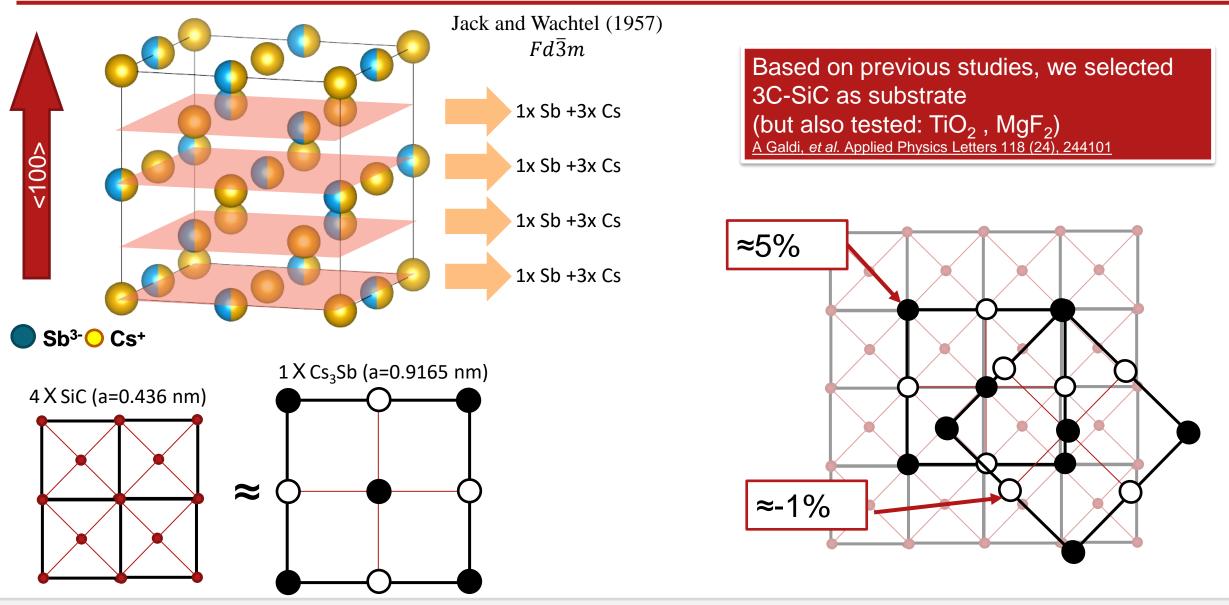






## $\bigotimes$ Cs<sub>3</sub>Sb structure and possible epitaxial relations









Reflection High Energy Electron Diffraction

(RHEED)

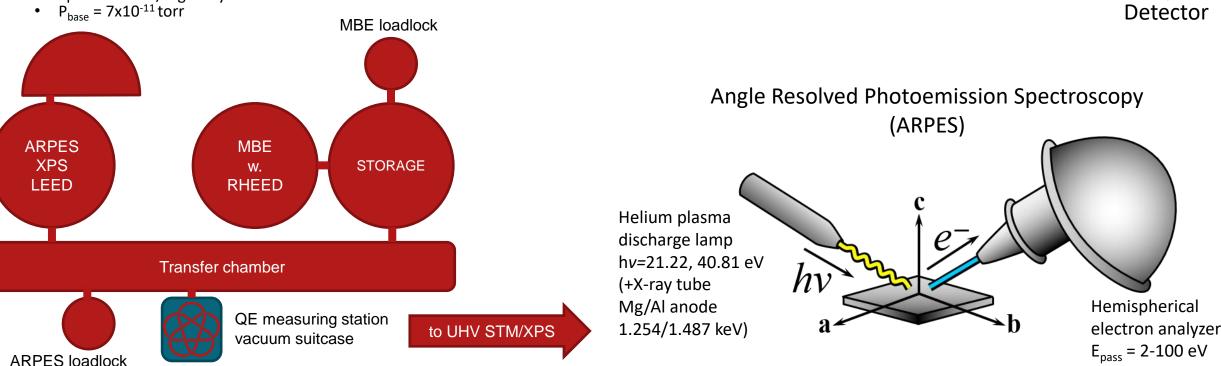
Sample

15kV e<sup>-</sup>gun

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#### PARADIM Thin Film User Facility

- Molecular Beam Epitaxy System
  - In Operando high energy electron diffraction (RHEED)
  - $P_{base} = 2x10^{-9}$  torr
- Sample Transfer System
  - In Situ Quantum Efficiency Station (biased pickup coil)
  - $P_{base} = 1 \times 10^{-9} \text{ torr}$
- ARPES/XPS System
  - Scientia DA30 electron analyzer
  - Fermi Helium Plasma discharge lamp
  - Specs XR50 AI/Mg X-ray source

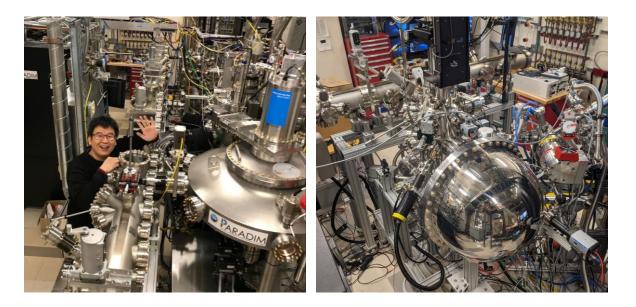




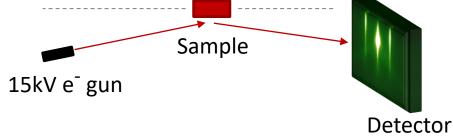


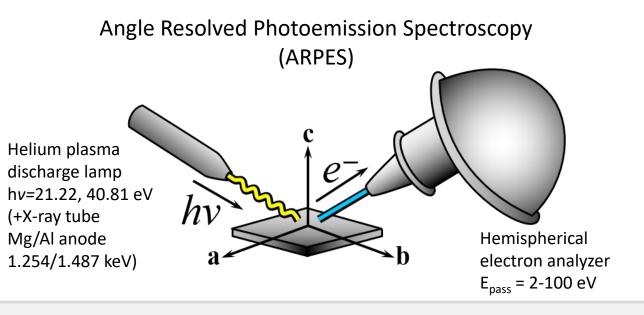
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  - Fermi Helium Plasma discharge lamp
  - Specs XR50 Al/Mg X-ray source
  - $P_{base} = 7x10^{-11} torr$



Reflection High Energy Electron Diffraction (RHEED)



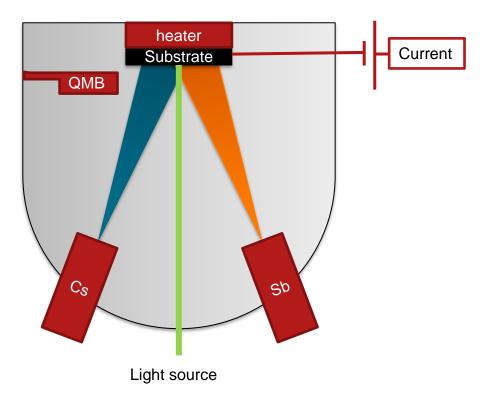




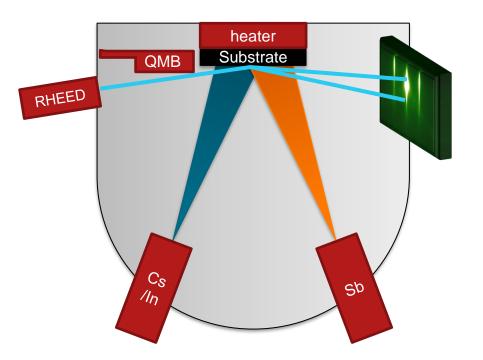
## The experiment



Typical photocathode growth: Photocurrent monitored Quantum efficiency oriented



Our growth method: RHEED monitored Structure oriented

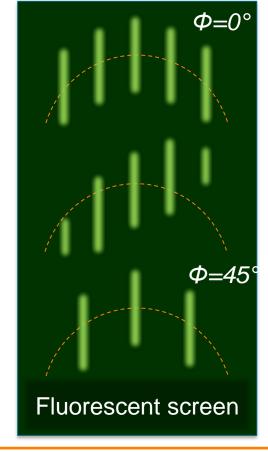




## Information provided by RHEED

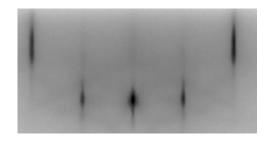


Single crystal k<sub>out</sub> k<sub>in</sub> Θ

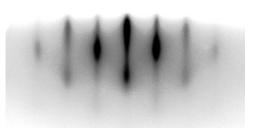


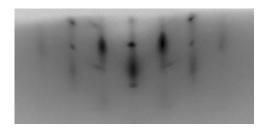
By rotating the sample around its surface normal, we intersect different sets of reciprocal space rods

- Real-time
- Sub-ML sensitivity
- Qualitative probe of surface roughness and crystallinity



Single crystal High coherence





Film Reduced coherence Roughened surface

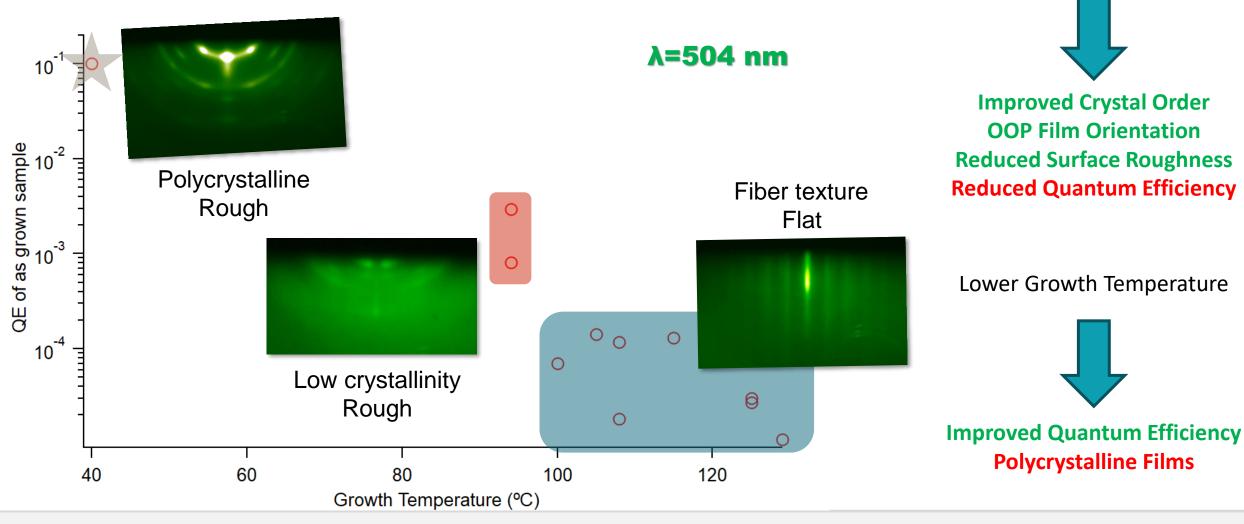
Film Polycrystalline domains/impurities





Higher Growth Temperature

- Cs-Sb co-deposition on SiC substrates
  - -Cs:Sb ratio = 6:1 (as measured by Quartz Crystal Microbalance)

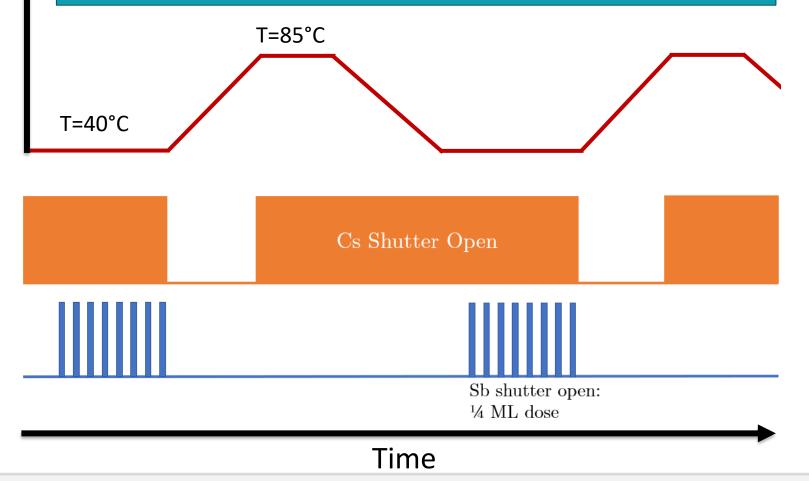








• **<u>High</u>** temperature Cs anneal to improve crystallinity

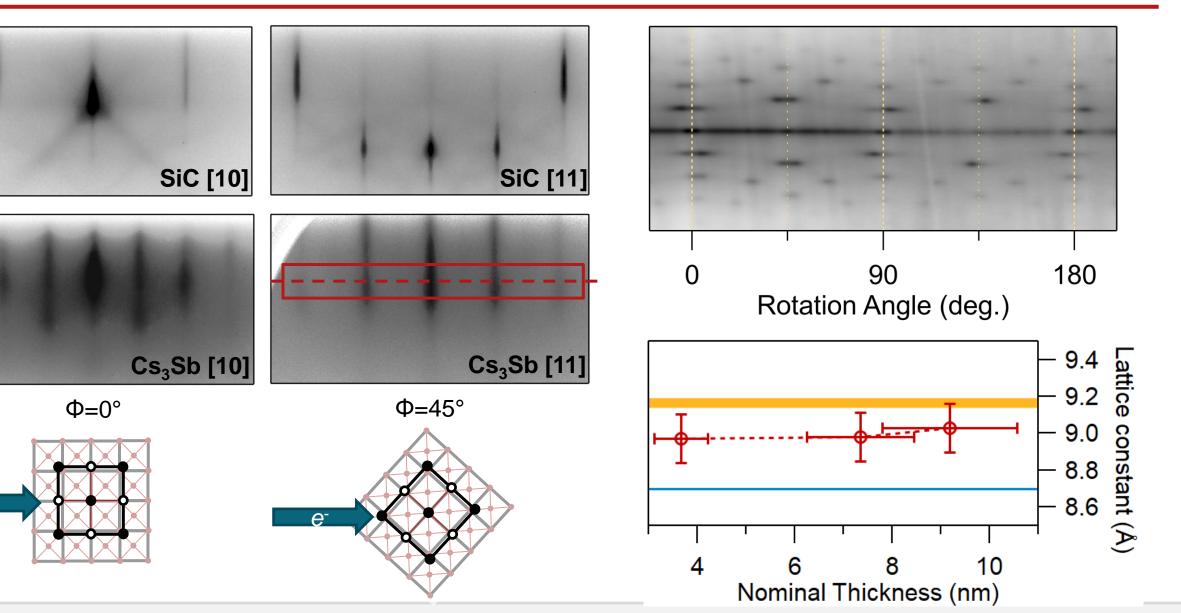








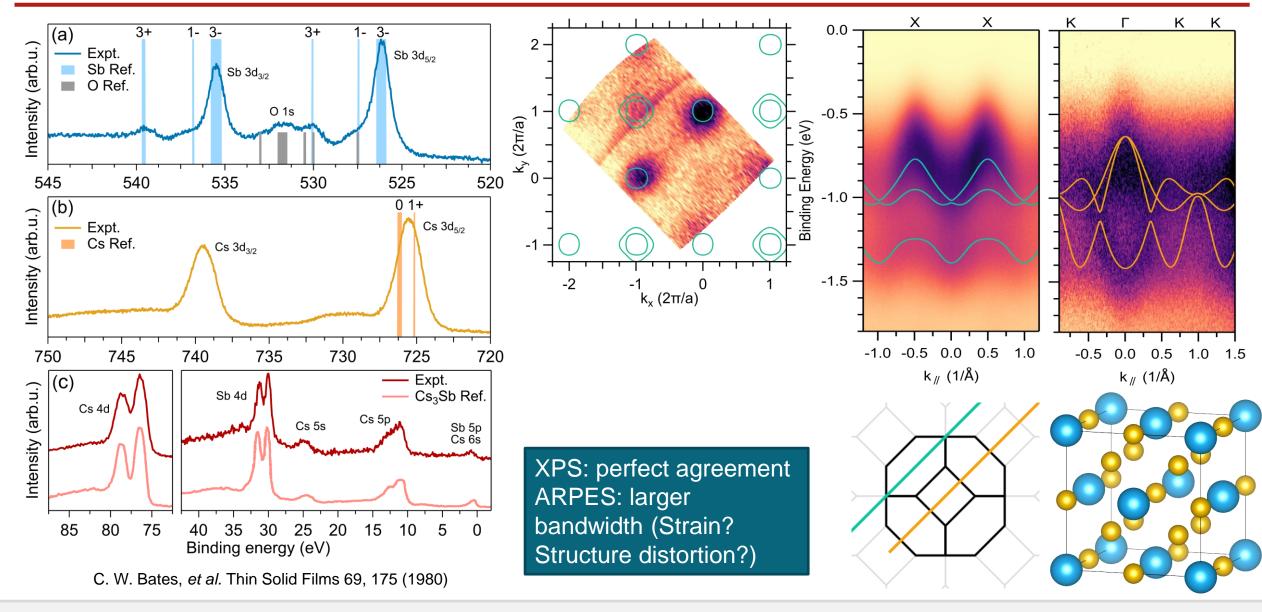
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## It really is Cs<sub>3</sub>Sb: XPS and ARPES

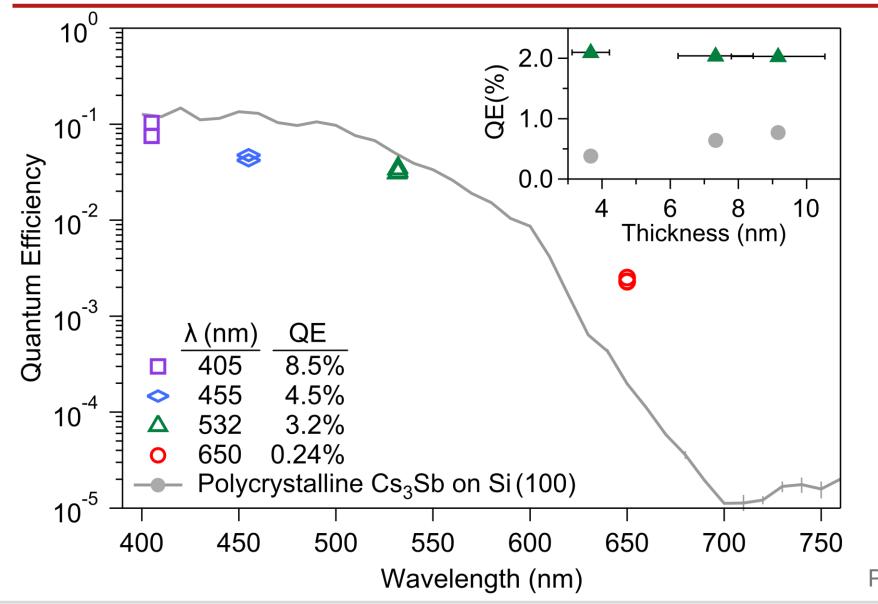






#### High efficiency in the ultrathin limit





Grey line and dots represent the data from a codeposited  $Cs_3Sb$ sample grown by photocurrent-monitored codeposition.

#### Enhanced QE:

- At the photoemission threshold
- At small thickness

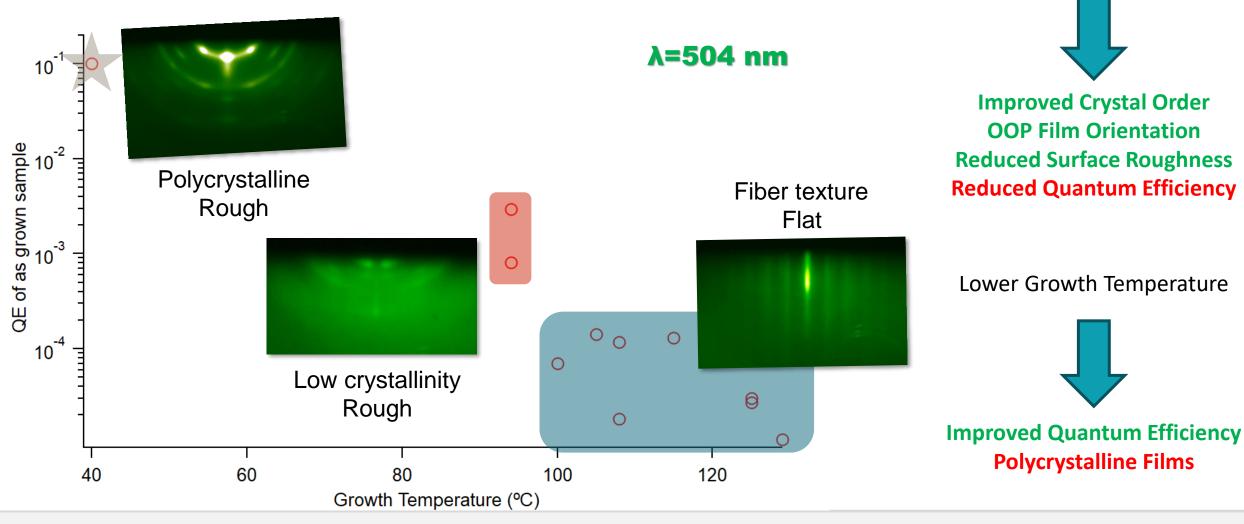
C.T. Parzyck, A. Galdi *et al.* Physical Review Letters 128, 114801





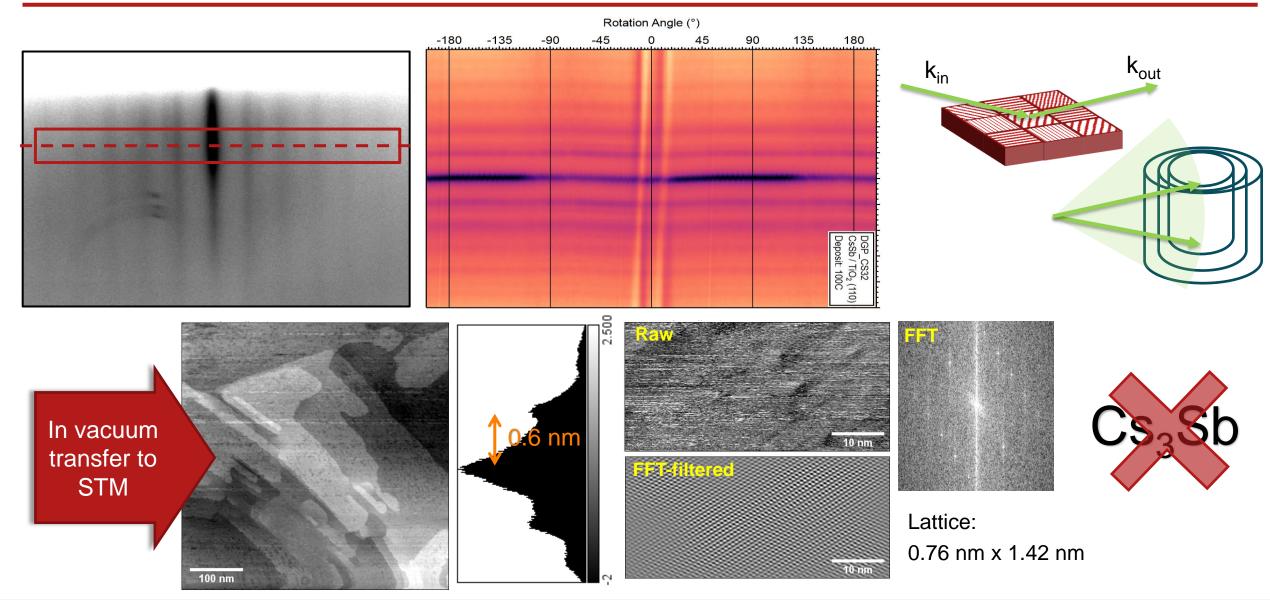
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## Flat co-deposited samples

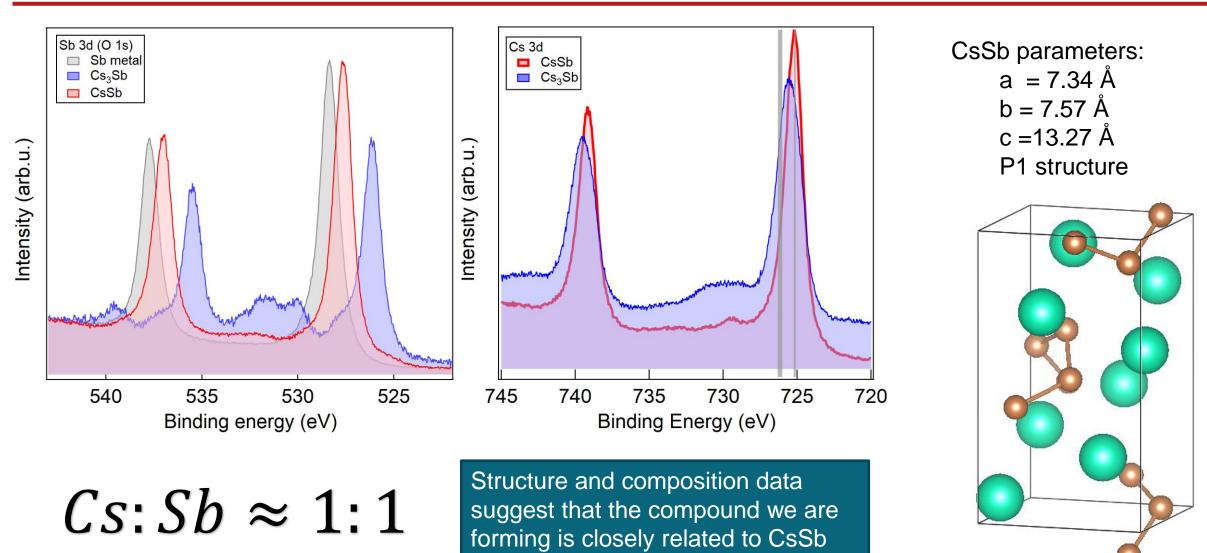






## Flat co-deposited samples



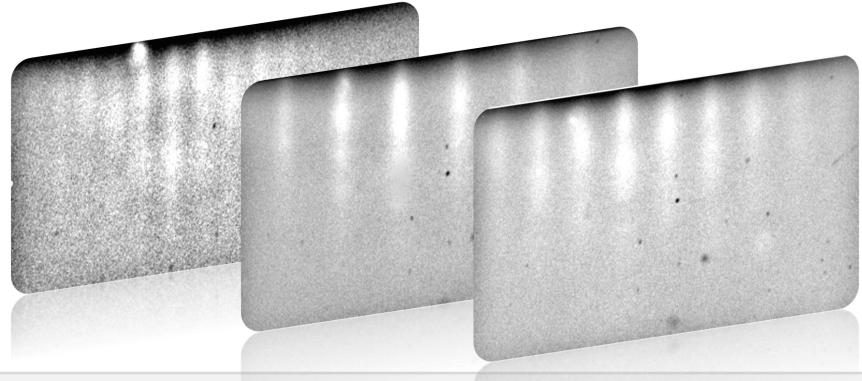






#### **PHOEBE: PHO**tocathode **E**pitaxy and **B**eam **E**xperiments laboratory





 Study of epitaxial Cs<sub>3</sub>Sb and CsSb samples: spectral response, lifetime, oxygen resistance, mean transverse energy





## Conclusions



- Epitaxy of Cs<sub>3</sub>Sb is achieved using molecular beam epitaxy via monitoring the sample structure with RHEED
- State-of-the-art MBE machines and in-situ RHEED allow to explore various growth regimes and efficient optimization of the samples beyond quantum efficiency
- High throughput:
  - -PARADIM experiments: 59 samples grown in 27 days (24h per day)
  - -PHOEBE: 75 Cs-Sb samples grown between 09/2021 and 08/2022
- Structure-oriented growth identifies an interesting phase: CsSb
  - -Atomically smooth
  - -Easily achievable via codeposition
  - -QE ~1% at 400 nm
  - -Robust against oxidation



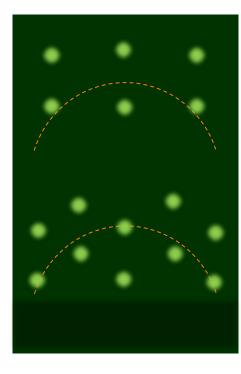
## Information provided by RHEED



Epitaxial island growth



Transmission pattern: Streaks turn into spots



#### Polycrystalline islands





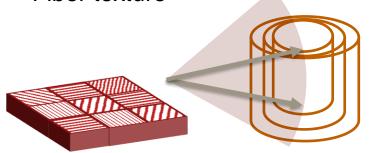


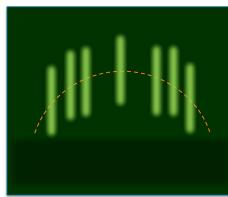
Textured film



No rotation dependence if the texture axis is out-ofplane (uniaxial) Rotation dependence if the texture axis is inplane (biaxial)

Fiber texture









## **Epitaxial Relationship**



